

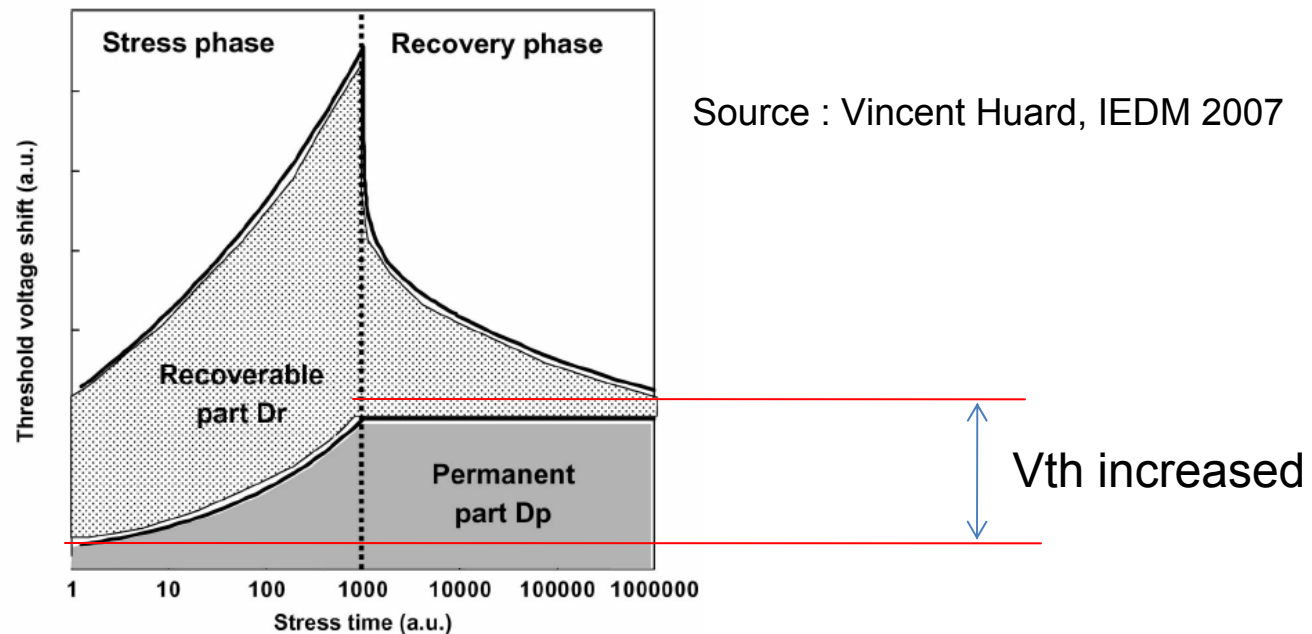
Extended Burn-in for V_{th} variation reduction using NBTI

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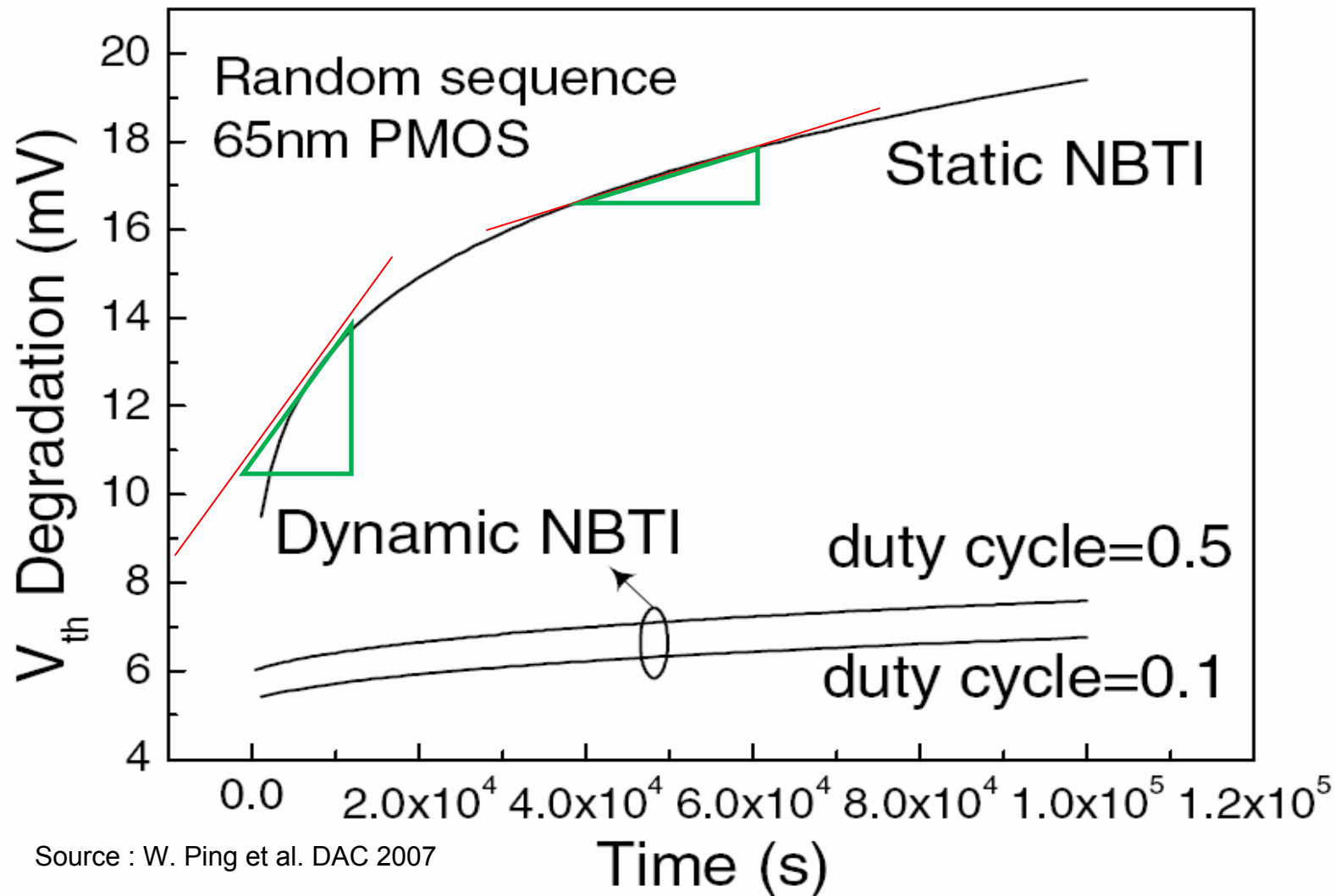
Advisor : Prof. Puneet Gupta

What is NBTI ?

- NBTI : Negative Bias Temperature Instability
- V_{th} varies on PMOS device
 - V_{th} increases with negative bias, $V_{gs} = -V_{dd}$
 - But recovers with zero bias, $V_{gs} = 0$



Time dependence





Source : W. Ping et al. DAC 2007

NBTI threats

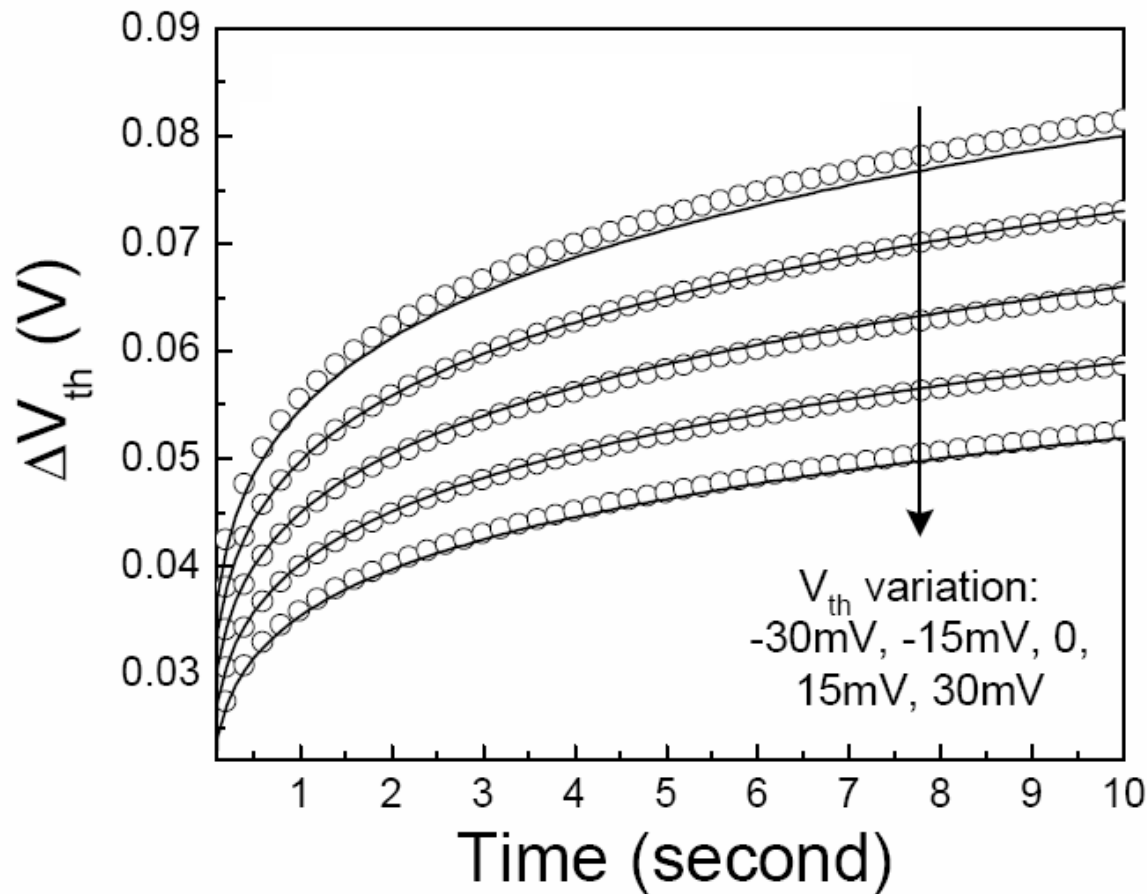
• ΔV_{th} -NBTI  as
CMOS scales



• Circuits reliability 
• Circuits lifetime 

- Krishnan, IEDM 2003
 - 10% I_{dsat} to 5% RO frequency degradation
- Pagaduan, IRPS 2000
 - FPGA performance degradation due to NBTI
 - Propagation delay 2.5%
- Neeraj, IEDM 2005
 - Degradation depends on configuration and application.
 - $V_{error} > 7$ mV (maximum allowed error=7.8mV) for a 64 bit DAC.
- J.C. Lin, IEDM 2006
 - SRAM read margin decrease as a result of NBTI stress.
 - Limit NBTI impact using a less “read margin” dominant design.

Observations



ΔV_{th} process \equiv ΔV_{th} NBTI
 ΔV_{th} process + ΔV_{th} NBTI
 \Rightarrow Overall process variation reduced

Source : W. Ping et al. DAC 2007

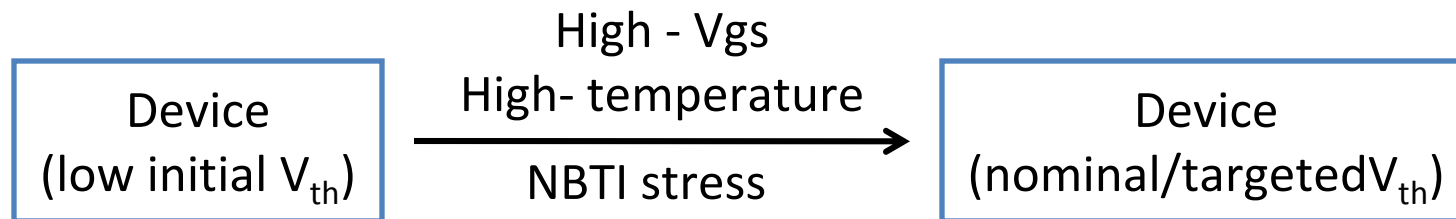
Opportunity

- ΔV_{th} is 40% at 2009 and increasing (ITRS).
- ΔV_{th} can be reduced by an intentional NBTI stress

Table DESN9a Design for Manufacturability Technology Requirements—Near-term Years

Year of Production	2007	2008	2009	2010	2011	2012	2013	2014	2015
Normalized mask cost from public and IDM data	1.0	1.3	1.7	2.3	3.0	3.9	5.1	6.6	8.7
% V_{dd} variability: % variability seen in on-chip circuits	10%	10%	10%	10%	10%	10%	10%	10%	10%
% V_{th} variability: doping variability impact on V_{th} , (minimum size devices, memory)	31%	35%	40%	40%	40%	58%	58%	81%	81%
% V_{th} variability: includes all sources	33%	37%	42%	42%	42%	58%	58%	81%	81%
% V_{th} variability: typical size logic devices, all sources	16%	18%	20%	20%	20%	26%	26%	36%	36%
% CD variability	12%	12%	12%	12%	12%	12%	12%	12%	12%
% circuit performance variability circuit comprising gates and wires	46%	48%	49%	51%	60%	63%	63%	63%	63%
% circuit total power variability circuit comprising gates and wires	56%	57%	63%	68%	72%	76%	80%	84%	88%
% circuit leakage power variability circuit comprising gates and wires	124%	143%	186%	229%	255%	281%	287%	294%	331%

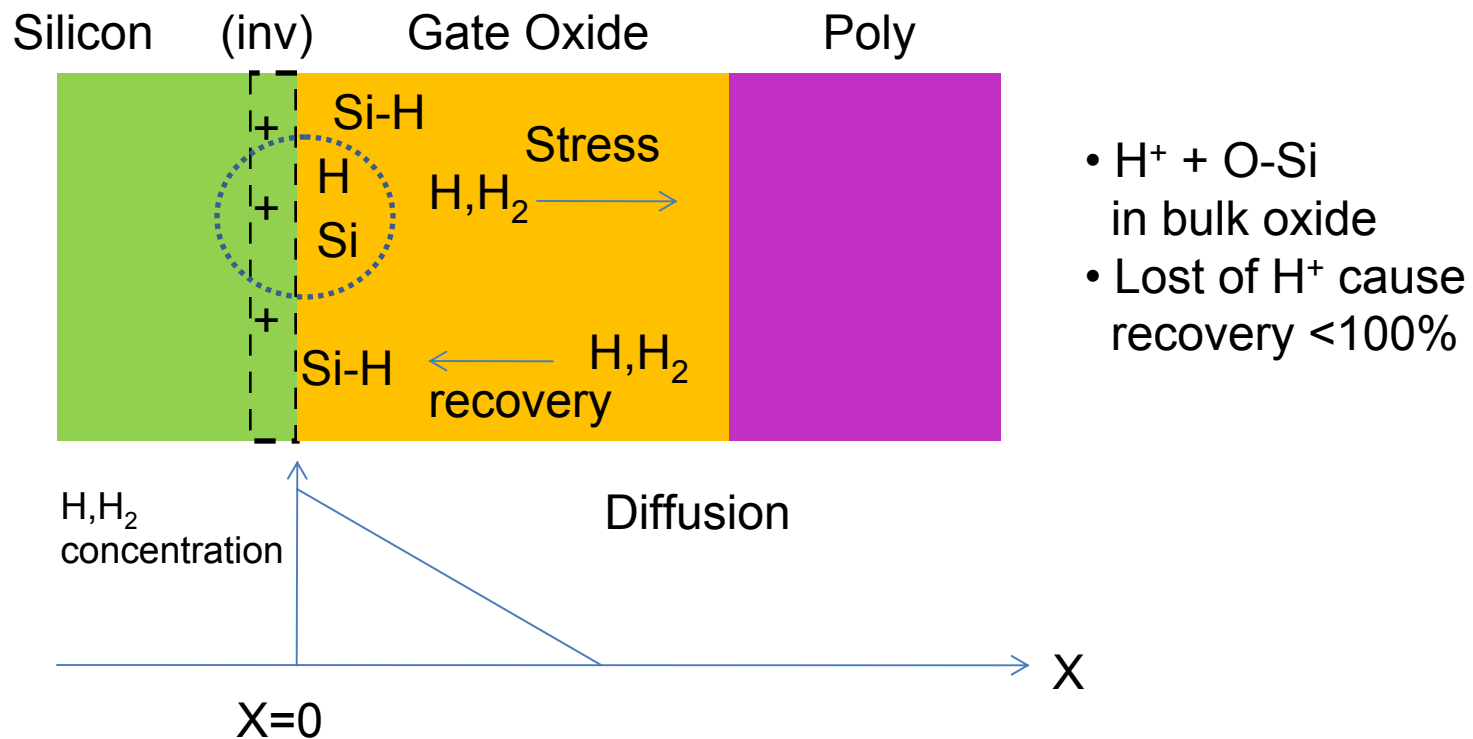
Proposed Burn-in flow



- Difference between targeted V_{th} and initial V_{th} provides “room” for NBTI stress.
- Lowering initial V_{th} may lead to higher initial V_{th} variation.
- Burn-in process and initial V_{th} has to be design carefully for optimum results.

Reaction-diffusion model

- Interface traps generated when device is stressed (negative bias)



Model Formulation

$$\frac{dN_{IT}}{dt} = k_F(N_o - N_{IT})P - k_R N_H N_{IT}$$

Reaction

$$\frac{dN_H}{dt} = D_H \frac{d^2 N_H}{dx^2}$$

Diffusion

Stress:

$$\Delta V_{th}(t) = (K_v(t - t_0)^{1/2} + \sqrt[2n]{\Delta V_{th}(t_0)})^{2n}$$

Recovery:

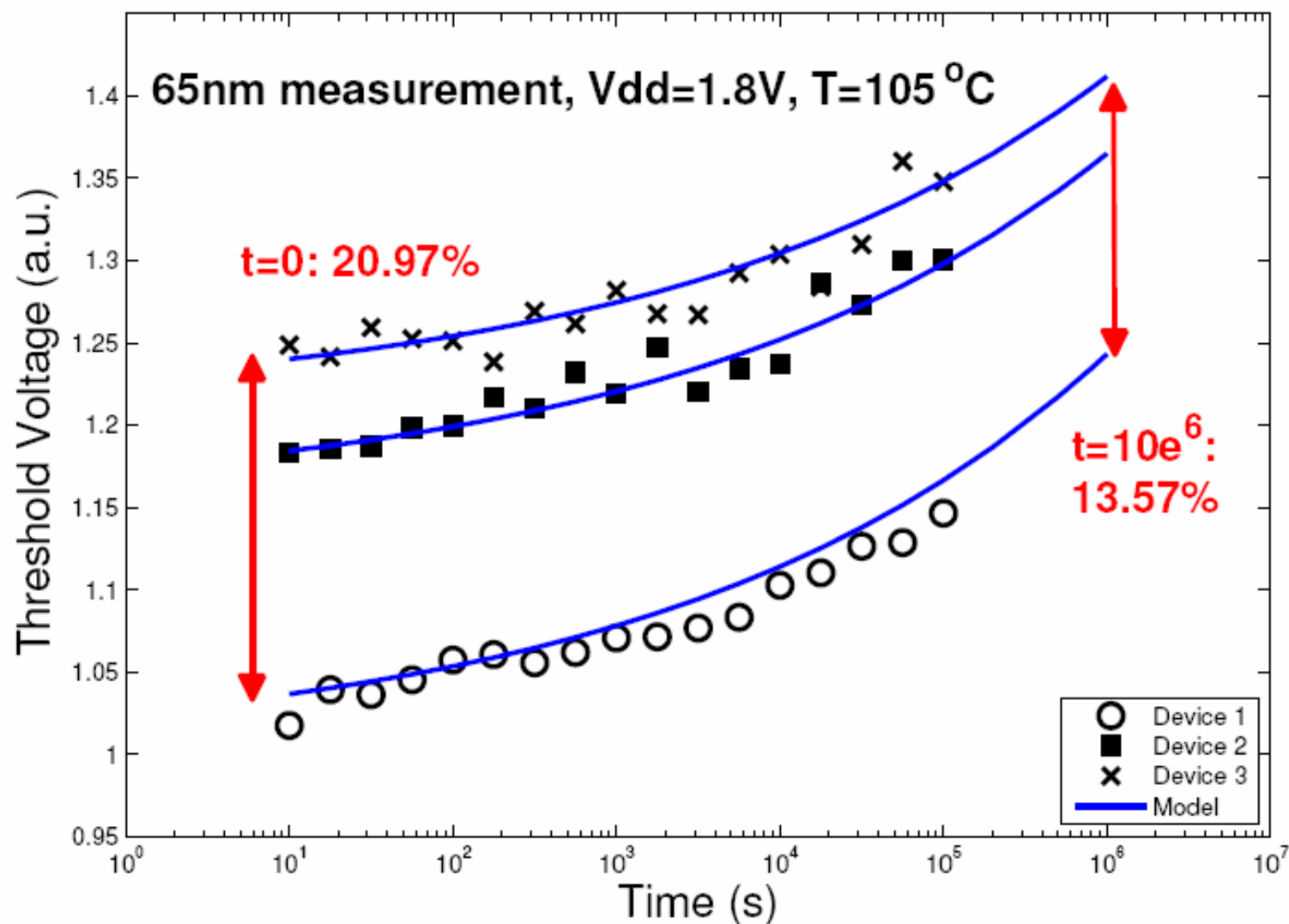
$$\Delta V_{th}(t) = \Delta V_{th}(t_1) \left(1 - \frac{2\xi_1 t_e + \sqrt{\xi_2 C(t - t_1)}}{(1 + \delta)t_{ox} + \sqrt{Ct}} \right)$$

Source : W. Ping et al. DAC 2007

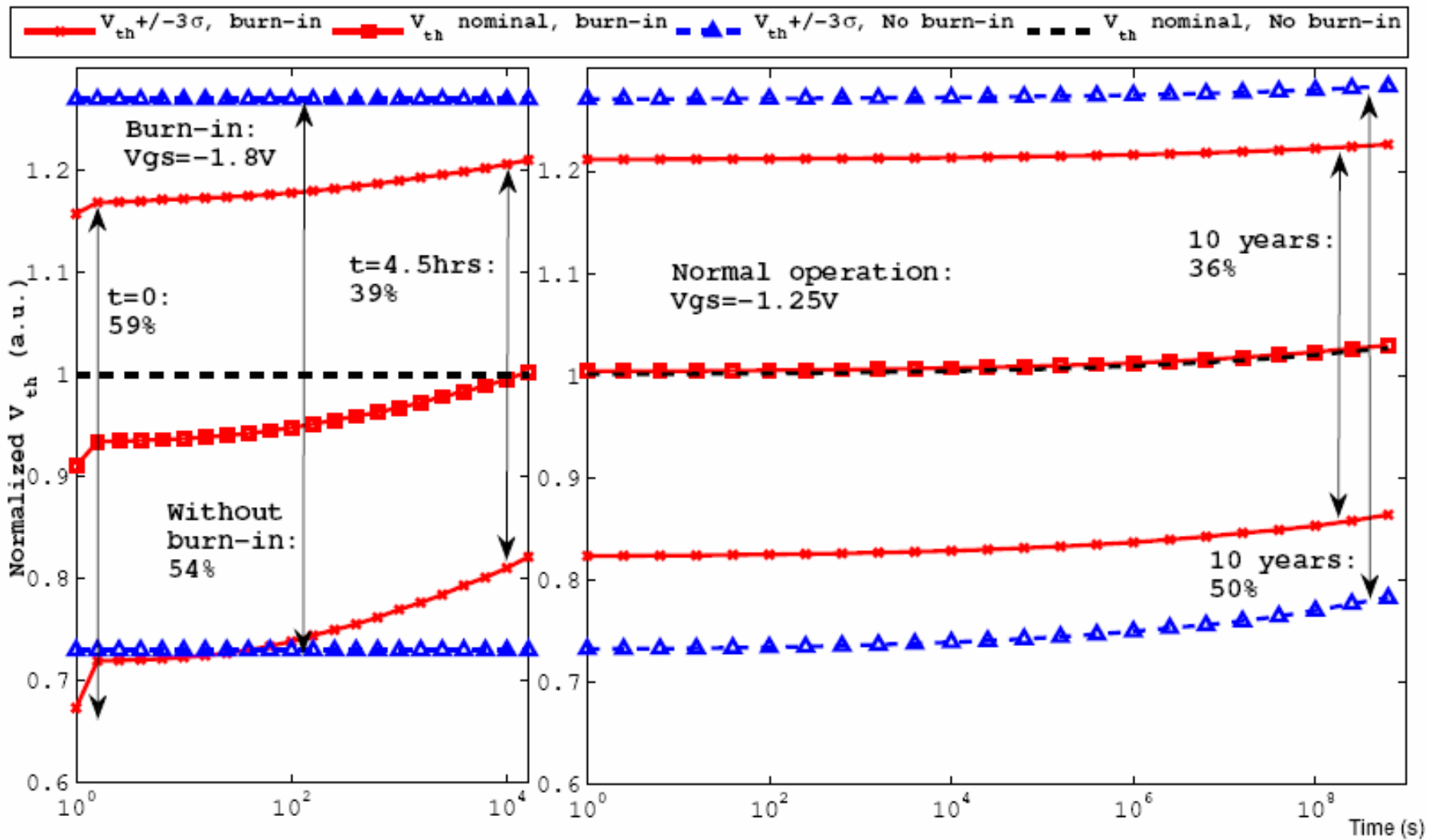
Combine both stress and recovery :

$$\Delta V_{th-nbti} = \left[\frac{(V_{gs} - V_{th}) K_1 * e^{K_2(V_{gs} - V_{th})}}{1 - \beta_t} \right]^{1/3}, \beta_t = 1 - \frac{K_3}{K_4 + K_5 t}$$

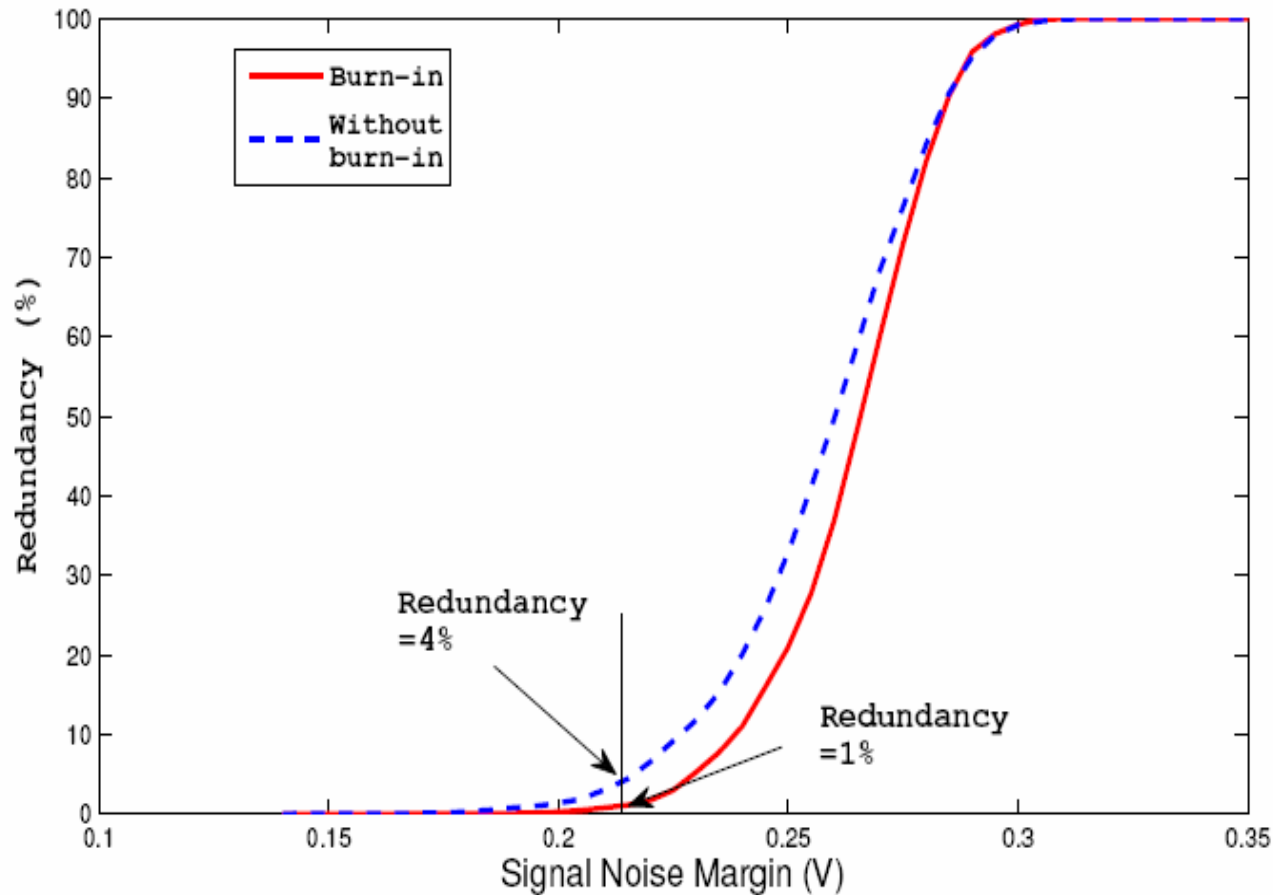
“Burn-in” with negative bias



PMOS burn-in under high DC stress



Case study 1



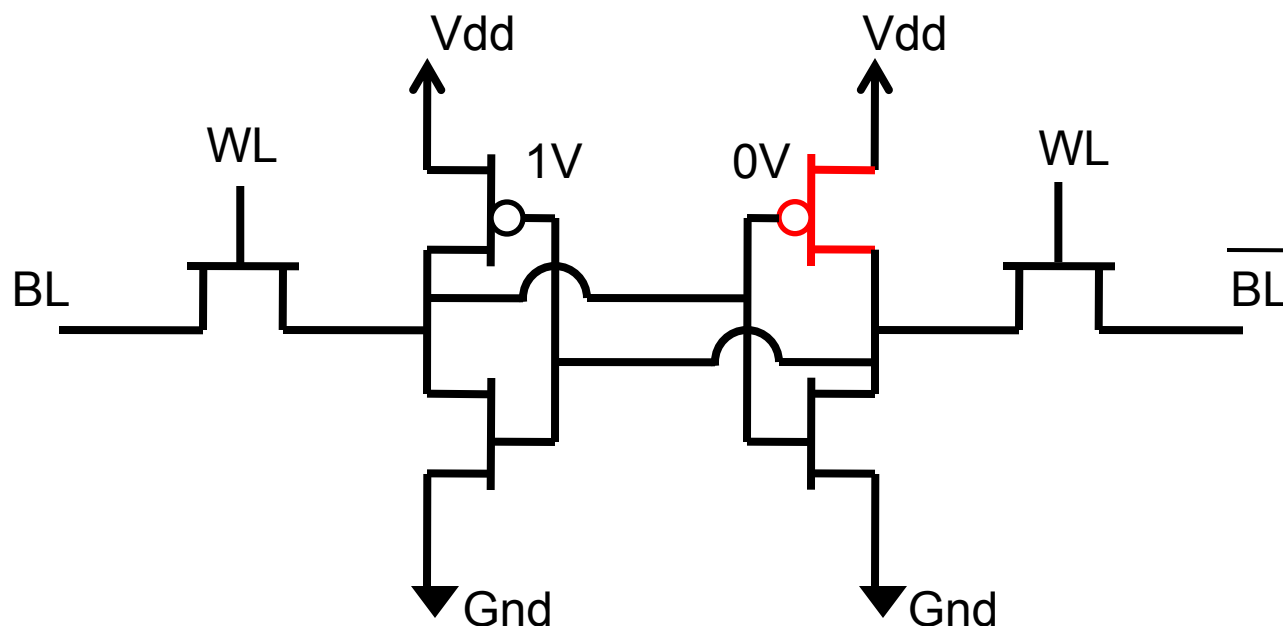
SPICE Monte Carlo simulation on 6T SRAM .

3000 samples,

NMOS
 $\Delta V_{th}=27\%$

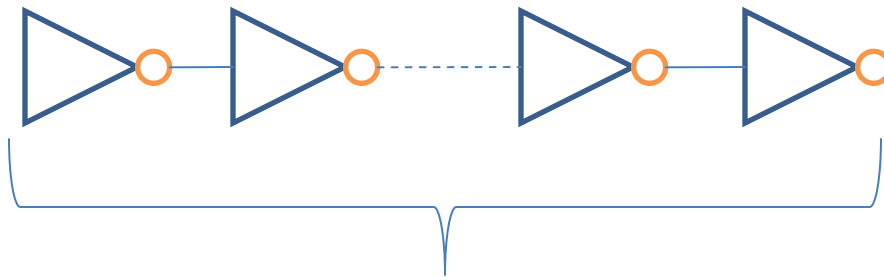
PMOS
 $\Delta V_{th}=27\%$ (initial)
 $\Delta V_{th}=17\%$ (4.5 hours burn-in)

Burn-in example



- Data bit =0 “stress” PMOS on right
- Data bit =1 “stress” PMOS on left
- Flipping data bit frequently : NBTI on both sides
- Lower V_{th} device will degrade faster => V_{th} mismatch reduced

Case study 2



11 stages inverter chain

SPICE Monte Carlo simulation results (3000 samples)

	Without burn-in	NBTI burn-in
Mean Delay (ps)	154.7	154.6
Delay variation (ps)	10.3	8.1

Summary

- NBTI induce parametric shift, threaten circuit reliability and lifetime.
- 4.5 hours burn-in reduces V_{th} variation from 27% (initial) => 17% (after burn-in)

On going work

- Generation of input vectors to bias internal PMOS in digital circuits.
- Analog circuit case study – “burn-in” to reduce design effort on battling V_{th} mismatch.
- Proof-of-concept silicon data.